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شبكة المعلومات الجامعية

التوثيق الالكتروني والميكرو فيلم

جامعة عين شمس

التوثيق الالكتروني والميكرو فيلم

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بالرسالة صفحات
لم ترد بالأصل

PREPARATION AND CHARACTERIZATION OF TRANSPARENT CONDUCTIVE OXIDE LAYER

A THESIS

Submitted to

Institute of Graduate Studies & Research

Department of Materials Science

In Partial Fulfillment

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Master of Materials Science



BY

MOHAMED MAHMOUD HUSSEIN

**B.Sc. In Chemistry, 1992, Faculty of Science
University of Alexandria**

University of Alexandria

2000

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SUPERVISORS

1. Prof. Mohamed Abd Allah Elgamal
Professor of Physics of Materials
Institute of Graduate Studies & Research
Alexandria University

2. Dr. Samir El Attway
Assistant Professor of Electronic Materials
Materials Science Department
Institute of Graduate Studies & Research
Alexandria University

3. Dr. Moataz M. Soliman
Lecturer of Electronic Materials
Materials Science Department
Institute of Graduate Studies & Research
Alexandria University

To my parents

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